



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 1092**  
Hiroto YUKAWA et al. : Docket No. 2004\_0499  
Serial No. 10/810,902 : Group Art Unit 1752  
Filed March 29, 2004 : Examiner Sin J. Lee

POSITIVE-WORKING CHEMICAL-  
AMPLIFICATION PHOTORESIST  
COMPOSITION

**Mail Stop: Amendment**

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**RESPONSE**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Official Action dated April 8, 2005, please amend the present application as follows: